For Semiconductor & Microelectronics Fabrication Processes

# ASSURE CLEANLINESS & CONSISTENT HIGH PERFORMANCE

Fluid purity is essential in semiconductor fabrication and microelectronics manufacturing and processing, such as wet etch and clean (WEC), photolithography, and chemical mechanical polishing (CMP). Also, transistors continue to shrink to unimaginable sizes, and capturing the tiniest particles in the nanometer range is critical for effective micro-contamination control.

GORE<sup>®</sup> Microfiltration Media offers a unique combination of the highest retention and flow unmatched by other filtration material suppliers. Our membrane assures repeatable high performance, consistent quality, and exceptional cleanliness in critical filter applications.

# Materials Science Innovation & Expertise in Filtration Technology

Our unparalleled expertise in manufacturing expanded polytetrafluoroethylene (ePTFE) and controlling its microstructure allows us to tailor membranes to increase retention and enable greater throughput or impart specific characteristics required for their intended use (Figure 1).

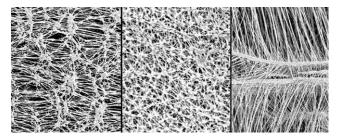


Figure 1: Gore ePTFE membrane structures under extreme magnification.



Gore is more than a membrane company — we are also an expert in filtration technology. For more than 40 years, we have delivered air, gas, liquid, and particle filtration solutions to help our partners purify processes, increase yields, and control costs.

We continue to set the industry standard in the liquid filtration market for membranes that bring high quality, high performance and reliability in the most critical semiconductor and microelectronics fabrication steps. In addition, we continue to develop new membranes as chip design gets finer, enabling filter manufacturers to keep up with industry needs and challenges to improve process yields.



#### **GORE®** Microfiltration Media

For Semiconductor & Microelectronics Fabrication Processes

## **Typical Applications**

- Semiconductor Manufacturing Processes
- Microelectronics Fabrication
- High Purity Chemical Production

#### Features

- Clean, non-shedding membranes
- High chemical and thermal resistance
- Hydrophobic and hydrophilic membranes
- Unique ePTFE microstructure with uniform membrane properties
- Available in various pore size ratings from 0.015 to 10 μm
- Membrane consistency from roll to roll and lot to lot

### **Benefits**

- Proven higher liquid flow rate at a given retention level
- Consistent high quality and repeatable high performance
- Reliably filters nanometer-level particles and harmful contaminants
- Reduce wafer defects and enhance process yields
- Decades of proven successful performance and reliability in many applications

# **Ordering Information**

GORE<sup>®</sup> Microfiltration Media are designed to fit many critical applications and microfiltration device design formats (Table 1). Our membranes are available in a wide range of pore sizes, retention levels, and flow rates that can be customized to meet your exact needs and requirements (Table 2). We also offer membrane discs in custom sizes for diverse applications.

For more information or to order our membranes for semiconductor and microelectronics fabrication processes, visit **gore.com/micromedia**.



#### **Table 1: Membrane Offerings**

Materials Construction	Pore Reference Size (µm)	Capabilities/Intended Use		
Hydrophobic (ePTFE)				
Membrane	0.015 to 10	Aggressive chemical and solvent-based applications		
Laminate PP Net	0.1 to 1.0	Laminate for added support and strength		
Hydrophilic				
Membrane	0.1 to 10	Water-based processes		

#### **Table 2: Membrane Properties**

			Bubble Point		Typical Flow Time	
Pore Size <sup>1</sup> (µm)	Gore Part Number <sup>2</sup>	Thickness (µm)	Liquid	kPa	Liquid	Seconds
Hydrophobic (ePTFE)	I					
0.02	SM0-00002	> 15	60% IPA	>700	IPA	< 1300
0.03	SM0-00003	>10	60% IPA	> 550	IPA	< 1200
0.05	SM0-00005	>10	EtOH	> 225	MeOH	< 300
0.1	SM0-00010	> 20	EtOH	> 155	MeOH	< 140
0.2	SM0-00020	> 35	EtOH	>100	MeOH	<100
0.45	SM0-00050	> 35	EtOH	> 63	MeOH	< 55
1	SM0-00100	< 120	IPA	> 24	IPA	(50) <sup>3</sup>
5	SM0-00500	< 100	IPA	>13	IPA	(20) <sup>3</sup>
10	SM0-00A00	< 100	IPA	>6	IPA	(10) <sup>3</sup>
Hydrophilic (ePTFE)						
0.1	HSM0-00010	> 20	EtOH	> 135	Water	< 160
0.2	HSM0-00020	> 20	Water	> 230	Water	< 60
0.5	HSM0-00050	> 20	Water	> 135	Water	< 25
1	HSM0-00100	> 20	Water	> 67	Water	< 12
5	HSM0-00500	< 80	IPA	> 13	IPA	< 15
10	HSM0-00A00	< 80	IPA	> 6	IPA	< 9
Laminate (Phobic/PP	Net)					
0.1	SM5-00010	>100	EtOH	>160	MeOH	< 250
0.2	SM5-00020	>100	EtOH	>107	MeOH	< 140
0.5	SM5-00050	>100	EtOH	> 63	MeOH	< 75
1	SM5-00100	> 90	EtOH	> 39	MeOH	< 28

1. Standard membranes

2. Membrane width is 270  $\pm$  5 mm

3. Data for reference

Information in this publication corresponds to W. L. Gore & Associates' current knowledge on the subject. It is offered solely to provide possible suggestions for user experimentation. It is NOT intended, however, to substitute for any testing the user may need to conduct to determine the suitability of the product for the user's particular purposes. Due to the unlimited variety of potential applications for the product, the user must determine BEFORE production use, that the product is suitable for the intended application and is compatible with other component materials. The user is solely responsible for determining the proper amount and placement of the product. Information in this publication may be subject to revision as new knowledge and experience become available. W. L. Gore & Associates cannot anticipate all variations in actual end user conditions, and therefore, makes no warranties and assumes no liability in connection with any use of this information. No information in this publication is to be considered as a license to operate under or a recommendation to infringe any patent right.

NOTICE — USE RESTRICTIONS APPLY. Not for use in food, drug, cosmetic or medical device manufacturing, processing, or packaging operations.

GORE, Together, improving life, and designs are trademarks of W. L. Gore & Associates. © 2023 W. L. Gore & Associates, Inc.

